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On The Cover: V. M. Donnelly, J. Guha, and L. Stafford, *Critical Review: Plasma-Surface Reactions and the Spinning Wall Method*, *Journal of Vacuum Science & Technology, A*, 29(1), p. 010801-1 (2011). The spinning wall method allows the complex chemistry on surface exposed to plasmas to be revealed. In the artist's depiction, atoms impinging on the surface react to form molecules that desorb and are detected a short time later. Kelly Williams, Thomas Shea and John Costales created the cover image.